

13-15 April 2010

Annex Hall  
Pacifico Yokohama  
Yokohama, Japan

# Photomask Japan 2010

*Symposium on*

## Photomask and NGL Mask Technology XVII

*Symposium Chair:*

Toshiyuki Horiuchi  
Tokyo Denki University

**Abstract Due Date:  
November 2009**

**Camera-Ready Abstract  
Due Date:  
February 2010**

**Manuscript Due Date:  
March 2010**

Concrete information will be announced at the 2<sup>nd</sup> Call for Papers.

Camera-ready abstracts and manuscripts are required of all accepted applicants and must be submitted in English

*Organized by*



*Co-organized by*



For more information, contact:

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**P**hotomask Japan 2010 is the 17th international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and investigators from Japan, USA, and all over the world in the field of photomasks, NGL masks, and related technologies to discuss recent progress, applications, and future trends. The conference program will feature invited papers, contributed papers, poster sessions, and a rump session with panel discussion. Display opportunities will be provided to mask manufacturing materials, and equipment companies.

*Papers are solicited on the following and related topics:*

- **Materials of and for Photomasks**
- **Fabrication Process Steps and Equipments for Photomasks (process and equipments for developing, etching, cleaning etc.)**
- **Photomask Writing Tools and Technologies**
- **Metrology Tools and Technologies**
- **Inspection Tools and Technologies**
- **Repairing Tools and Technologies**
- **Mask Data Preparations**
- **EDA and DFM for Photomasks**
- **Photomasks with RET: PSM, Masks with OPC**
- **Photomask-relating Lithography Technologies**
- **NGL Masks and Applications: EUV, Nano-imprint etc.**
- **Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.**

### *Abstract Submissions*

All authors are *strongly encouraged* to submit their abstract by the due date, November 2009, using the “Electronic Abstract Submission System” via the PMJ Web.

Abstract submission Web page will be opened from November 2009 at:

<http://www.photomask-japan.org/>

Further information and instruction will be available from 2nd Announcement & Call for Papers, which will be published around September, 2009

**\*Please do not send the abstract by e-mail, fax or post.**

### *Conference Site*

Conference site of Photomask Japan 2010 will be “Annex Hall” at Pacifico Yokohama as same as Photomask Japan 2009